

61-100967(4)

1. Insulating Substrate
 2. Ion Implanted Insulating Layer
 3. Source Region / Drain Region
 4. Channel Region
 5. Gate Insulating Layer
 6. Gate Electrode
 7. Inter layer Insulating Layer
 8. Source Electrode / Drain Region
 9. Non-Single Crystal Silicon Layer
 10. Resist Layer
 11. Oxygen Ion Beam or
Nitrogen Ion Beam
 12. Impurity Ion Beam
 13. Mask Insulating Layer
- A: Source / Channel Boundary or
Drain / channel Boundary

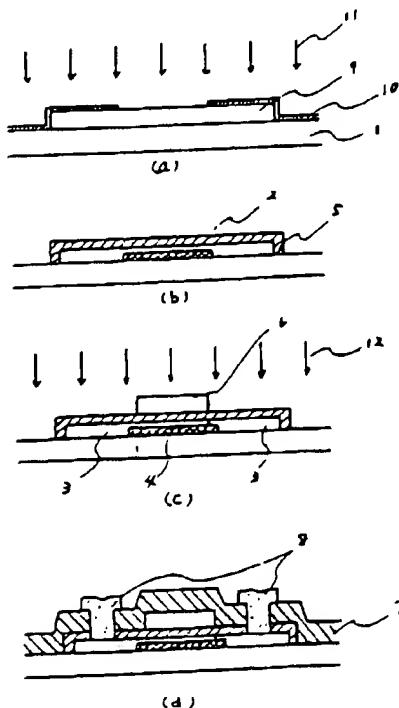


FIG. 3

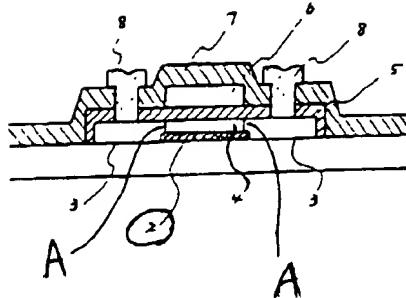


FIG. 7

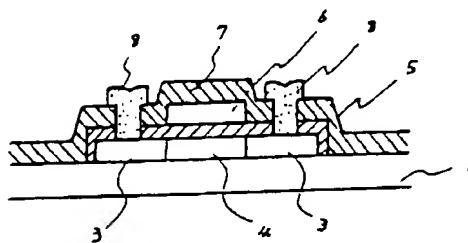


FIG. 2 (PRIOR ART)

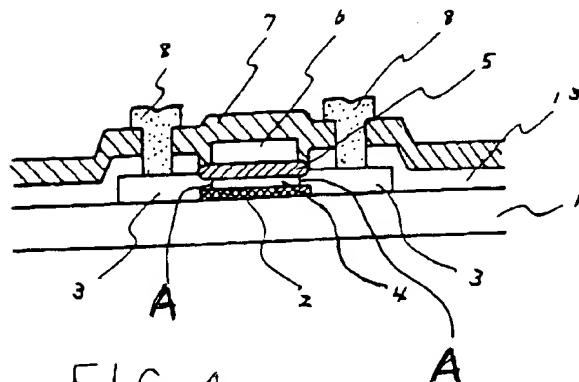


FIG. 4

Appendix I